

Electronic Acknowledgement Receipt

EFS ID:	1207286
Application Number:	10672778
Confirmation Number:	9717
Title of Invention:	Atomic layer deposition (ALD) method with enhanced deposition rate
First Named Inventor:	Chih-Ta Wu
Customer Number:	47390
Filer:	Daniel R. McClure
Filer Authorized By:	
Attorney Docket Number:	252016-3000
Receipt Date:	19-SEP-2006
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Application Type:	Utility
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Submitted with Payment	yes
Payment was successfully received in RAM	\$ 50
RAM confirmation Number	879
Deposit Account	

File Listing:

Document Number	Document Description	File Name	File Size(Bytes)	Multi Part	Pages
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1	Fee Worksheet (PTO-875)	fee-info.pdf	8132	no	2
Warnings:					
Information:					
Total Files Size (in bytes):			8132		
<p>This Acknowledgement Receipt evidences receipt on the noted date by the USPTO of the indicated documents, characterized by the applicant, and including page counts, where applicable. It serves as evidence of receipt similar to a Post Card, as described in MPEP 503.</p> <p><u>New Applications Under 35 U.S.C. 111</u> If a new application is being filed and the application includes the necessary components for a filing date (see 37 CFR 1.53(b)-(d) and MPEP 506), a Filing Receipt (37 CFR 1.54) will be issued in due course and the date shown on this Acknowledgement Receipt will establish the filing date of the application.</p> <p><u>National Stage of an International Application under 35 U.S.C. 371</u> If a timely submission to enter the national stage of an international application is compliant with the conditions of 35 U.S.C. 371 and other applicable requirements a Form PCT/DO/EO/903 indicating acceptance of the application as a national stage submission under 35 U.S.C. 371 will be issued in addition to the Filing Receipt, in due course.</p>					